

**Amendments to the Specification:**

Please replace the paragraph on page 1, line 17, with the following amended paragraph:

CROSS-REFERENCE TO RELATED APPLICATIONS

This application is a continuation-in-part of U.S. Application Serial No. 10/164,327 filed June 5, [[2003]] 2002 by Kenneth Collins et al., entitled EXTERNALLY EXCITED TORROIDAL PLASMA SOURCE WITH MAGNETIC CONTROL OF ION DISTRIBUTION and assigned to the present assignee.

The following applications contain subject matter related to the present application:

U.S. Patent Application Serial No. 10/646,458, filed August 22, 2003, entitled "PLASMA IMMERSION ION IMPLANTATION APPARATUS INCLUDING A PLASMA SOURCE HAVING LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE" by Kenneth Collins, et al.; U.S. Patent Application Serial No. 10/646,533, filed August 22, 2003, entitled "PLASMA IMMERSION ION IMPLANTATION PROCESS USING A PLASMA SOURCE HAVING LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE" by Kenneth Collins et al.; U.S. Patent Application Serial No. 10/646,532, filed August 22, 2003, entitled "PLASMA IMMERSION ION IMPLANTATION APPARATUS INCLUDING A CAPACITIVELY COUPLED PLASMA SOURCE HAVING LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE" by Kenneth Collins, et al.; U.S. Patent Application Serial No. 10/646,612, filed August 22, 2003, entitled "PLASMA IMMERSION ION IMPLANTATION PROCESS USING A CAPACITIVELY COUPLED PLASMA SOURCE HAVING LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE" by Kenneth Collins et al.; U.S. Patent Application Serial No. 10/646,528, filed August 22, 2003, entitled "PLASMA IMMERSION ION IMPLANTATION APPARATUS INCLUDING AN INDUCTIVELY COUPLED PLASMA SOURCE HAVING LOW DISSOCIATION AND

LOW MINIMUM PLASMA VOLTAGE" by Kenneth Collins, et al.; U.S. Patent Application Serial No. 10/646,467, filed August 22, 2003, entitled "PLASMA IMMERSION ION IMPLANTATION PROCESS USING AN INDUCTIVELY COUPLED PLASMA SOURCE HAVING LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE" by Kenneth Collins, et al.; U.S. Patent Application Serial No. 10/646,526, filed August 22, 2003, entitled "PLASMA IMMERSION ION IMPLANTATION SYSTEM INCLUDING A CAPACITIVELY COUPLED PLASMA SOURCE HAVING LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE" by Kenneth Collins, et al.; U.S. Patent Application Serial No. 10/646,460, filed August 22, 2003, entitled "PLASMA IMMERSION ION IMPLANTATION SYSTEM INCLUDING AN INDUCTIVELY COUPLED PLASMA SOURCE HAVING LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE" by Kenneth Collins, et al. --